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01/22/02

PATENT NUMBER and  
ISSUE DATE

U.S. UTILITY Patent Application

APPL NUM 10056316	FILING DATE 01/22/2002	CLASS 205	SUBCLASS 640	GAU 1741	EXAMINER PARSONS
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\*\*APPLICANTS:

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\*\*CONTINUING DATA VERIFIED:

\*\* FOREIGN APPLICATIONS VERIFIED:

PG-PUB	DO NOT PUBLISH <input type="checkbox"/>	RESCIND <input type="checkbox"/>	ATTORNEY DOCKET NO
Foreign priority claimed 35 USC 119 conditions met		<input type="checkbox"/> yes <input type="checkbox"/> no <input type="checkbox"/> yes <input type="checkbox"/> no	AMAT/6339/CMP/CMP/RKK
Verified and Acknowledged Examiners's initials			
TITLE : Endpoint detection for electro chemical mechanical polishing and electropolishing processes U.S. DEPT. OF COMM./PAT. & TM-PTO-436L(Rev. 12-94)			

NOTICE OF ALLOWANCE MAILED		Assistant Examiner	CLAIMS ALLOWED	
			Total Claims	Print Claim for O.G
ISSUE FEE		DRAWING		
Amount Due	Date Paid	Sheets Drwg.	Figs.Drwg.	Print Fig.
<input type="checkbox"/> TERMINAL DISCLAIMER		Primary Examiner		Application Examiner
		PREPARED FOR ISSUE		
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